



Our Reference: SHN-146-A

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Karl-Heinz Schuster
Serial No.: 10/566,849
Filing Date: 05/09/2006
Examiner/Art Unit: Unknown/2851
Title: MICROLITHOGRAPHIC PROJECTION EXPOSURE APPARATUS AND
IMMERSION LIQUID THEREFORE

CERTIFICATE OF TRANSMISSION			
I hereby certify that this correspondence is being transmitted by First Class U.S. Mail to the U.S. Patent and Trademark Office on the date shown below			
Signature	<i>Lorelei Jeanne Oye</i>		
Name	Lorelei Jeanne Oye	Date	November 20, 2006

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

The references listed in the attached form PTO-1449 are cited pursuant to Rule 37 C.F.R. 1.56 to meet the duty to disclose to the Patent Office all information known to the inventor, attorney or any other person who is substantively involved in the preparation or prosecution of the application or who is associated with the inventor, with the assignee or with anyone to whom there is an obligation to assign the application.

These references constitute all the information of which the individuals pursuant to 37 C.F.R. § 1.56(c) are currently aware.

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Respectfully submitted,

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FORM PTO-1449
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

Complete if Known

Application No.	10/566,849
Filing Date	May 9, 2006
First Named Inventor	Karl-Heinz Schuster
Art Unit	2851
Examiner Name	
Attorney Docket No.	SHN-146-A

U.S. Patent Documents

EXAMINER INITIALS	Cite No. ¹	Document No.	Publication Date mm-dd-yyyy	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (If Known)			
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	XP-0023300789 "WATER-BASED 193nm IMMERSION LITHOGRAPHY" Online!, Bruce Smith, 28 January 2004 (2004-01-28), XP 002329291 retrieved from the Internet: URL: http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20ri%20microstepper%20efforts_Smith.pdf retrieved on 2005-05-24, p. 14: NA>1.lens material: SiO2, p. 22: n(liquid lens)>1.6>n(SiO2)

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not considered. Include a copy of this form with next communication to applicant.